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APPLICATION NO.	FILING DATE	FIRST NAMED INVENTOR	ATTORNEY DOCKET NO.	CONFIRMATION NO
09/540,610	03/31/2000	James E. Nulty	16820.P097	2171
7:	590 01/09/2002			
Blakely Sokoloff Taylor & Zafman 12400 Wilshire Boulevard Seventh Floor			EXAMINER CHU, CHRIS C	
			2815	7
			DATE MAILED: 01/09/2002	

Please find below and/or attached an Office communication concerning this application or proceeding.



, ·		Application No.	Applicant(s)		
•		09/540,610	NULTY ET AL.		
Office Action Summary		Examiner	Art Unit		
		Chris C. Chu	2815		
Period fo	The MAILING DATE of this communication r Reply	on appears on the cover sheet v	vith the correspondence address		
THE I - Exter after - If the - If NO - Failu - Any r	DRTENED STATUTORY PERIOD FOR F MAILING DATE OF THIS COMMUNICAT usions of time may be available under the provisions of 37 (SIX (8) MONTHS from the mailing date of this communicat period for reply specified above is less than thirty (30) days period for reply is specified above, the maximum statutory re to reply within the set or extended period for reply will, by eply received by the Office later than three months after thi d patent term adjustment. See 37 CFR 1.704(b).	ION. CFR 1.136(a). In no event, however, may a ion. s, a reply within the statutory minimum of the period will apply and will expire SIX (6) MC statute, cause the application to become A	reply be timely filed irty (30) days will be considered timely. INTHS from the mailing date of this communication. ABANDONED (35 U.S.C. § 133).		
1)⊠	Responsive to communication(s) filed o	n <u>October 4, 2001</u> .			
2a)⊠	This action is FINAL . 2b)	This action is non-final.			
3)	Since this application is in condition for allowance except for formal matters, prosecution as to the merits is closed in accordance with the practice under Ex parte Quayle, 1935 C.D. 11, 453 O.G. 213.				
Disposit	on of Claims				
4)⊠	Claim(s) 25 - 39 is/are pending in the ap	pplication.			
	4a) Of the above claim(s) is/are w	ithdrawn from consideration.			
5)	Claim(s) is/are allowed.				
6)⊠	Claim(s) 25 - 39 is/are rejected.				
7)	Claim(s) is/are objected to.				
8)	Claim(s) are subject to restriction	and/or election requirement.			
Applicat	ion Papers				
9)[The specification is objected to by the Ex	aminer.			
10)	The drawing(s) filed on is/are: a)[accepted or b) objected to by	the Examiner.		
	Applicant may not request that any objection	on to the drawing(s) be held in abe	eyance. See 37 CFR 1.85(a).		
11)	The proposed drawing correction filed on	is: a) approved b)	disapproved by the Examiner.		
	If approved, corrected drawings are require	* *			
12)	The oath or declaration is objected to by	the Examiner.			
Priority	under 35 U.S.C. §§ 119 and 120				
13)	Acknowledgment is made of a claim for	foreign priority under 35 U.S.C	C. § 119(a)-(d) or (f).		
a)	All b) Some * c) None of:				
	1. Certified copies of the priority doc	uments have been received.	•		
	2. Certified copies of the priority doc	uments have been received in	Application No		
*:	Copies of the certified copies of the application from the Internation See the attached detailed Office action for	nal Bureau (PCT Rule 17.2(a)).		
14) 🔲	Acknowledgment is made of a claim for d	omestic priority under 35 U.S.	C. § 119(e) (to a provisional application).		
15)⊠	a) ☐ The translation of the foreign langua Acknowledgment is made of a claim for c	• • • • • • • • • • • • • • • • • • • •			
Attachme	• •	. 🗂 .			
1) 🔛 Noti	ce of References Cited (PTO-892)	4) Intervie	w Summary (PTO-413) Paper No(s).		



DETAILED ACTION

Response to Amendment

1. The amendment filed on October 4, 2001 has been received and entered in this office action.

Amend claims: 25, 26, and 34.

Claim Rejections - 35 USC § 102

2. The following is a quotation of the appropriate paragraphs of 35 U.S.C. 102 that form the basis for the rejections under this section made in this Office action:

A person shall be entitled to a patent unless -

(b) the invention was patented or described in a printed publication in this or a foreign country or in public use or on sale in this country, more than one year prior to the date of application for patent in the United States.

3. Claims 25 and $27 \sim 39$ are rejected under 35 U.S.C. 102(b) as being anticipated by Dennison et al.

Regarding claim 25, Dennison et al. discloses the etch stop layer (20) is silicon nitride (column 3, line 35).

Regarding claim 27, note Fig. 2 of Dennison et al., where the reference shows a structure (10), comprising: a conductive layer (12 and column 3, lines $29 \sim 33$) disposed over a substrate; a first insulating layer (18) on the conductive layer; a contact region (the area of 34) in the first insulating layer; at least one insulating spacer (18) in the contact region adjacent to the first insulating layer (see Fig. 2); and an etch stop material (20 and



column 3, line 35) over the first insulating layer and adjacent to the insulating spacer (see Fig. 2), the etch stop material being distinct from the insulating spacer (see Fig. 2 and column 3, lines $32 \sim 38$).

Regarding claim 28, Fig. 2 of Dennison et al., where the reference shows the insulating spacer (18) has a substantially rectangular profile in the contact region (see Fig. 2).

Regarding claims 29 and 36, Fig. 2 of Dennison et al., where the reference shows the insulating spacer (18) has a surface portion in the contact region without overlying etch stop material (see Fig. 2).

Regarding claims 30 and 37, Fig. 2 of Dennison et al., where the reference shows the insulating spacer (18) surface portion without overlying etch stop material comprises an insulating spacer surface portion most distant from the substrate (see Fig. 2).

Regarding claim 31, Fig. 2 of Dennison et al., where the reference shows the insulating spacer (18) has a surface portion in the contact region without overlying etch stop material (see Fig. 2).

Regarding claims 32 and 38, Fig. 2 of Dennison et al., where the reference shows a structure (10), further comprising a second insulating layer (28) on the etch stop layer and over the conductive layer (see Fig. 2).

Regarding claims 33 and 39, Fig. 2A of Dennison et al., where the reference shows a structure (10), further comprising a second conductive material (40) in the contact region (see Fig. 2A).

Regarding claim 34, Fig. 2 of Dennison et al., where the reference shows a structure, comprising the step of: a first electrically conductive material (24) formed in



and/or on a surface of a substrate; a contact opening (the area of 34) in a region adjacent to a second electrically conductive material (the area of 40 in Fig. 2A) formed on the substrate; an electrically insulative spacer (18) in the contact opening adjacent to the second electrically conductive material (see Fig. 2); an etch stop material (20) over the electrically insulative spacer and the first and second electrically conductive materials (see Fig. 2), the etch stop material being distinct from the insulative spacer (see Fig. 2); a blanket layer (28) over the etch stop material; and an opening through a first part of the etch stop material to the first electrically conductive material (see Fig. 2).

Regarding claim 35, Fig. 2 of Dennison et al., where the reference shows the electrically insulative spacer (18) has a substantially rectangular cross-sectional shape in a plane that is substantially perpendicular to the substrate surface (see Fig. 2).

Claim Rejections - 35 USC § 103

- 4. The following is a quotation of 35 U.S.C. 103(a) which forms the basis for all obviousness rejections set forth in this Office action:
 - (a) A patent may not be obtained though the invention is not identically disclosed or described as set forth in section 102 of this title, if the differences between the subject matter sought to be patented and the prior art are such that the subject matter as a whole would have been obvious at the time the invention was made to a person having ordinary skill in the art to which said subject matter pertains. Patentability shall not be negatived by the manner in which the invention was made.
- 5. Claim 26 is rejected under 35 U.S.C. 103(a) as being unpatentable over Dennison et al. in view of Gonzalez.

Dennison et al. discloses the claimed invention except the etch stop layer is silicon dioxide. However, Gonzalez discloses the etch stop layer is silicon dioxide (31 in



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